

DESKTOP VACUUM INSTALLATION FOR FILM DEPOSITION BY THERMAL EVAPORATION

NVU TM TIS 01



Purpose:

Film deposition by thermal evaporation.

Special characteristics:

- Substrate processing in one technological cycle (single-sided processing):
60 x 48 mm – 1 pc.
- Microprocessing control system;
- Oil-free pumping system (turbomolecular pump 60 l/h);
- Consumed power not more than 4,5 kW;
- 1,5 m² area per one installation.

